

AMENDMENT TRANSMITTAL LETTER

Docket No. 29926/39487

Application No.	Filing Date	Examiner	Art Unit
10/613,331-Conf. #5070	July 3, 2003	Brook Kebede	2823

Applicant(s): In Haeng Lee et al.

Invention:

METHOD FOR FORMING METAL SILICIDE LAYER IN ACTIVE AREA OF

SEMICONDUCTOR DEVICE

TO THE COMMISSIONER FOR PATENTS

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

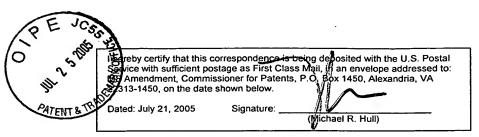
1		CLAIN	IS AS AMENI	DED			
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present		Rate		
Total Claims	28	- 31 =	0	х			
Independent Claims	2	- 3 =	0	x			
Multiple Depend	dent Claims (ch	eck if applicab	le)				
Other fee (please specify): Extension for response within second month AND Supplemental Information Disclosure Statement						450.00 180.00	
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:						630.00	
x Large Entity					Small Entity	•	
No additional fee is required for this amendment.							
	ge Deposit Acc copy of this she			n the a	mount of \$	•	
X A check in the amount of \$ 630.00 to cover the filing fees is enclosed.							
Payment by	credit card. Fo	orm PTO-2038	3 is attached.				
× The Director is hereby authorized to charge and credit Deposit Account No13-2855							
as described below. A duplicate copy of this sheet is enclosed.							
x Credit a	ny overpaymer	ıt.					
Charge	any additional fili	ng or application	on processing :	ees re	auired under :	37 CFR 1.16 and 1.17.	
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	A				Dated:	July 21, 2005	
Michael R. Hul	05.000						
Attorney Reg. N							
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(312) 474-6300							

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail, in an envelope addressed to: MS Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on the date shown below.

Dated: July 21, 2005

Signature:

_ (Michael R. Hull)



Docket No.: 29926/39487

(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: In Haeng Lee et al.

Application No.: 10/613,331

Confirmation No.: 5070

Filed: July 3, 2003

Art Unit: 2823

For: METHOD FOR FORMING METAL SILICIDE

LAYER IN ACTIVE AREA OF SEMICONDUCTOR DEVICE

Examiner: Brook Kebede

AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION

MS Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

INTRODUCTORY COMMENTS

In response to the Office Action dated February 23, 2005, please amend the above-identified U.S. patent application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 9 of this paper.